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REMARKS

Claims 1-24 are currently pending in the subject application and are presently under consideration. Claim 20 has been amended to be consistent with allowed claims 1-19 and 21-24. A listing of claims can be found on pages 2-5. Favorable reconsideration of the subject patent application is respectfully requested in view of the comments and amendments herein.

I. Rejection of Claim 20 Under 35 U.S.C. §102(e)

Claim 20 stands rejected under 35 U.S.C. §102(e) as being anticipated by Von Harrach *et al.* (US 2005/0054115 A1). It is respectfully submitted that this rejection be withdrawn for at least the following reason. Von Harrach *et al.* does not describe each and every element of the subject claims.

For a prior art reference to anticipate, 35 U.S.C. §102 requires that “*each and every element* as set forth in the claim is found, either expressly or inherently described, in a single prior art reference.” *In re Robertson*, 169 F.3d 743, 745, 49 USPQ2d 1949, 1950 (Fed. Cir. 1999) (quoting *Verdegaal Bros., Inc. v. Union Oil Co.*, 814 F.2d 628, 631, 2 USPQ2d 1051, 1053 (Fed. Cir. 1987)) (emphasis added).

The invention relates to a system and method for detecting, analyzing, and treating soft defects on a reticle in real-time. (See pg. 4, ll. 1-2). In particular, independent claim 20, as amended in accordance with allowed claims 1-19 and 21-24, recites: employing a Focused Ion Beam in a *non-reactive gas environment*; effecting a *phase shift in the signature present in the soft defect's chemical composition to a gaseous state*; and providing a continuous pump-out of *the gaseous signature* to remove the signature in gaseous form. Von Harrach *et al.* does not describe this aspect of the invention as claimed.

Von Harrach *et al.* discloses sample-taking of wafers in the production process. (See Abstract). Rather than a *non-reactive gas environment*, the cited reference utilizes iodine gas. (See paragraph 0020). In addition, the cited reference is silent with respect to a *signature present in the soft defect's chemical composition*, let alone a *phase shift*

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regarding such signature to a gaseous state. Furthermore, instead of removal of a *gaseous signature*, Von Harrach *et al.* discusses removal of SiH_2 , a gaseous compound. (See paragraph 0020). Von Harrach *et al.* does not describe these aspects of applicants' invention as recited in independent claim 20 and accordingly, this rejection should be withdrawn.

CONCLUSION

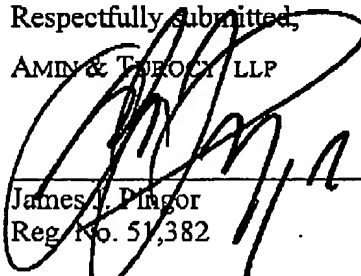
The present application is believed to be in condition for allowance in view of the above comments and amendments. A prompt action to such end is earnestly solicited.

In the event any fees are due in connection with this document, the Commissioner is authorized to charge those fees to Deposit Account No. 50-1063 [AMDP818US].

Should the Examiner believe a telephone interview would be helpful to expedite favorable prosecution, the Examiner is invited to contact applicants' undersigned representative at the telephone number below.

Respectfully submitted,

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